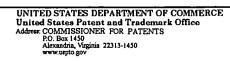


UNITED STATES PATENT AND TRADEMARK OFFICE



APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
09/847,658	05/02/2001	Wolfgang Singer	82704	7054	
7	590 06/24/2003				
Gerald T. Shekleton, Esq.			EXAMINER		
Welsh & Katz, Ltd. 120 S. Riverside Plaza, 22nd Floor			CHOI, WILLIAM C		
Chicago, IL 60606			ART UNIT	PAPER NUMBER	
			2873	·	

DATE MAILED: 06/24/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

- T				MC
	Applicatio	n No.	Applicant(s)	
. N. 4:	09/847,658	3	SINGER ET AL.	
Notic of Allowability	Examiner		Art Unit	
	William C.	Choi	2873	
The MAILING DATE of this comm. All claims being allowable, PROSECUTION ON Therewith (or previously mailed), a Notice of Allowand NOTICE OF ALLOWABILITY IS NOT A GRANT of the Office or upon petition by the applicant. Se	THE MERITS IS (OR REMAIN ance (PTOL-85) or other app OF PATENT RIGHTS. This	NS) CLOSED in this appropriate communication application is subject to	plication. If not includ will be mailed in due	ed course. THIS
1. This communication is responsive to Amel				
2. The allowed claim(s) is/are <u>1-3,7,19-25,27</u>		# = = = = = = = = = = = = = = = = = = =		
3. The drawings filed on <u>02 May 2001 and 07</u>				
 Acknowledgment is made of a claim for for a local a	reign priority under 35 0.5.C of the:	. 9 119(a)-(d) or (i).		
1. Certified copies of the priority	documents have been receiv	red.		
2. Certified copies of the priority	documents have been receiv	red in Application No	·	
Copies of the certified copies of	of the priority documents hav	re been received in this	national stage applica	ation from the
International Bureau (PCT I	Rule 17.2(a)).			
* Certified copies not received:				
5. Acknowledgment is made of a claim for do	• •	·	onal application).	
(a) The translation of the foreign langua	• •			
6. Acknowledgment is made of a claim for do	mestic priority under 35 U.S.	C. 99 120 and/or 121.		
Applicant has THREE MONTHS FROM THE "MA below. Failure to timely comply will result in ABA	ILING DATE" of this commu NDONMENT of this applicati	nication to file a reply colon. THIS THREE-MOI	omplying with the requ NTH PERIOD IS NOT	uirements noted EXTENDABLE.
7. A SUBSTITUTE OATH OR DECLARATIO INFORMAL PATENT APPLICATION (PTO-152)				NOTICE OF
8. CORRECTED DRAWINGS must be submi (a) including changes required by the No 1) hereto or 2) to Paper No.	tice of Draftsperson's Patent 			
(b) including changes required by the pro				
(c) including changes required by the atta	ached Examiner's Amendme	ent / Comment or in the	Office action of Paper	No
Identifying indicia such as the application numbers each sheet.	per (see 37 CFR 1.84(c)) should	d be written on the drawi	ngs in the front (not th	e back) of
 DEPOSIT OF and/or INFORMATION a attached Examiner's comment regarding REQUIF 				Note the
Attachment(s)				
 Notice of References Cited (PTO-892) Notice of Draftperson's Patent Drawing Reviews Information Disclosure Statements (PTO-1447) Examiner's Comment Regarding Requirement of Biological Material 	19), Paper No	4 ☐ Interview Summ 6 ☑ Examiner's Ame 8 ☑ Examiner's State 9 ☐ Other pps ☐	al Patent Application arry (PTO-413), Pape endment/Comment ement of Reasons for	r No

/**//**D *6/23/03* Page 2 *D8E//*

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EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Gerald Shekleton on 6/19/2003.

The application has been amended as follows:

1. Claim 36, line 3, after "claim" delete "26" and insert --20--. 1

Allowed Claims: 1-3, 7, 19-25, 27-32 and 34-42.

REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance: none of the prior art either alone or in combination disclose or teach of the claimed combination of limitations to warrant a rejection under 35 USC 102 or 103. Specifically, with respect to independent claim 1, none of the prior art alone or in combination disclose or teach of a projection lens as claimed, specifically wherein the gas chamber is constructed as an at least approximately plane-parallel manipulation chamber located between the lens arrangement and the image plane.

Specifically, with respect to independent claim 2, none of the prior art alone or in combination disclose or teach of a projection lens as claimed, specifically wherein the

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gas chamber is constructed as an at least approximately plane-parallel manipulation chamber located between the lens arrangement and the image plane.

Specifically, with respect to independent claim 3, none of the prior art alone or in combination disclose or teach of a projection lens as claimed, specifically wherein the gas chamber is constructed as an at least approximately plane-parallel manipulation chamber located between the lens arrangement and the image plane.

Specifically, with respect to independent claim 19, none of the prior art alone or in combination disclose or teach of a system for projection lens as claimed, specifically wherein the gas chamber is a manipulation chamber formed between adjacent planeparallel optical elements.

Specifically, with respect to independent claim 20, none of the prior art alone or in combination disclose or teach of a system for projection lens as claimed, specifically including an at least approximately plane-parallel manipulable gas interspace, for the purpose of removing field curvature, on a substrate, which is to be exposed, in a sixth optical group.

Specifically, with respect to independent claim 21, none of the prior art alone or in combination disclose or teach of a system for projection lens as claimed, specifically wherein the gas chamber is constructed between adjacent approximately plane-parallel optical elements to form a manipulation chamber.

Specifically, with respect to independent claim 29, none of the prior art alone or in combination disclose or teach of a method for producing microstructured components Application/Control Number: 09/847,658

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as claimed, specifically wherein the refractive index is manipulated by pressure changes and changes in gas composition.

Specifically, with respect to independent claim 37, none of the prior art alone or in combination disclose or teach of a projection lens for microlithography as claimed, specifically wherein the gas chamber is a manipulation chamber formed between adjacent plane-parallel optical elements.

Specifically, with respect to independent claim 38, none of the prior art alone or in combination disclose or teach of a projection lens for microlithography as claimed, specifically wherein the gas chamber is constructed between adjacent plane-parallel optical elements to form a manipulation chamber.

Specifically, with respect to independent claim 39, none of the prior art alone or in combination disclose or teach of a projection lens for microlithography as claimed, specifically wherein the gas chamber is constructed between adjacent approximately plane-parallel optical elements to form a manipulation chamber.

Specifically, with respect to independent claim 40, none of the prior art alone or in combination disclose or teach of a projection lens as claimed, specifically wherein the gas chamber is located between an end plate and the lens situated adjacent to the end plate.

Specifically, with respect to independent claim 41, none of the prior art alone or in combination disclose or teach of a projection lens as claimed, specifically wherein the gas chamber is located between an end plate and the lens situated adjacent to the end plate.

Specifically, with respect to independent claim 42, none of the prior art alone or in combination disclose or teach of a projection lens as claimed, specifically wherein the gas chamber is located between an end plate and the lens situated adjacent to the end plate.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

CONCLUSION

Any inquiry concerning this communication or earlier communications from the examiner should be directed to William C. Choi whose telephone number is (703) 305-3100. The examiner can normally be reached on Monday-Friday from about 9:00 am to 6 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Georgia Y. Epps can be reached on (703) 308-4883. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 305-3431 for regular communications and (703) 305-3432 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

w.c.

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William Choi Patent Examiner Art Unit 2873 June 19, 2003

Georgia Epps
Supervisory Patent Examiner
Technology Center 2800